



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

C/ #6
05/08/02
AS

In re Patent Application of

YAMAMURA *et al.*

Appln. No.: 09/924,116

Group Art Unit: tbd

Filed: August 8, 2001

Examiner: tbd

For: PHOTOCURABLE LIQUID RESIN COMPOSITION

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April 19, 2002

SUPPLEMENTAL PRELIMINARY AMENDMENT

Hon. Commissioner of Patents
Washington, D.C. 20231

Sir:

Prior to examination on the merits, please amend the application in the manner set forth below.

IN THE CLAIMS

Please enter new claims 33-42.

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Sub D1 → 33. (New) A photocurable resin composition comprising:
 (A) an epoxy compound having two or more alicyclic epoxy groups;
 (B) a cationic photopolymerization initiator;
 (C) dipentaerythritol penta(meth)acrylate;
 (D) a radical photopolymerization initiator; and
 (E) a polyol having three or more hydroxyl groups in one molecule.

C1 → 34. (New) The composition of claim 33, wherein said polyol is a polyether polyol.